

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Claims 4-7, 12-18 and 21-29 have been amended as follows:

Listing of Claims:

Claim 1 (original): A chitin oligomer composition and/or a chitosan oligomer composition characterized by containing 0.001 to 1000 ppm of fluorine atom.

Claim 2 (original): A chitin oligomer composition and/or a chitosan oligomer composition characterized by containing 0.001 to 1000 ppm of calcium atom.

Claim 3 (original): The chitin oligomer composition and/or the chitosan oligomer composition according to claim 1, wherein the content of the oligomer from a trimer to a decamer is 60% or more.

Claim 4 (currently amended): The chitin oligomer composition and/or the chitosan oligomer composition according to ~~any of claims 1 and 2~~ claim 1, wherein the content of the oligomer from a tetramer to a decamer is 40% or more.

Claim 5 (currently amended): The chitin oligomer composition and/or the chitosan oligomer composition according to ~~any one of claims 1 to 4~~ claim 1, wherein the amount of the composition dissolved in 100 g of water at 20°C is 2 to 20 g.

Claim 6 (currently amended): The chitin oligomer composition according to ~~any one of claims 1 to 5~~ claim 1, wherein the concentration of endotoxin is 100 EU/ml or less.

Claim 7 (currently amended): The chitin oligomer composition according to ~~any one of claims 1 to 6~~ claim 1, wherein the chitin oligomer and/or the chitosan oligomer is a chitin oligomer

composition.

Claim 8 (original): A process for preparing a chitin oligomer composition and/or a chitosan oligomer composition, the process comprising the step of adding hydrofluoric acid in a concentration of 20 to 95 wt% to a chitin-based material and/or a chitosan-based material.

Claim 9 (original): The process according to claim 8, wherein the concentration of hydrofluoric acid is 20 to 75 wt%.

Claim 10 (original): The process according to claim 8, wherein the concentration of hydrofluoric acid is 75 to 95 wt%.

Claim 11 (original): A process for preparing chitin oligomer composition and/or a chitosan oligomer composition, the process comprising the step of adding at least one of (A) hydrofluoric acid and (B) hydrohalogenated acid other than hydrofluoric acid, the process being characterized in that (C) the concentration of hydrofluoric acid is 1 to 75 wt% based on the total amount of hydrohalogenated acid other than hydrofluoric acid and hydrofluoric acid; and that (D) the concentration of hydrohalogenated acid other than hydrofluoric acid is 1 to 35 wt% based on the total amount of hydrohalogenated acid other than hydrofluoric acid and hydrofluoric acid.

Claim 12 (currently amended): The process according to ~~any one of claims 8 to 11~~ claim 8, wherein the liquid temperature in adding hydrofluoric acid or hydrohalogenated acid and hydrofluoric acid to the chitin-based material and/or the chitosan-based material is adjusted to -2 to 150°C.

Claim 13 (currently amended): The process according to ~~any one of claims 8 to 12~~ claim 8, wherein basic calcium salt is added, at a suitable time, to a solution containing the chitin-based

material and/or the chitsan-based material, hydrofluoric acid or hydrohalogenated acid other than hydrofluoric acid and hydrofluoric acid.

Claim 14 (currently amended): The process according to ~~any one of claims 8 to 13~~ claim 8 which includes a step of adding a hydrophilic organic solvent, at a suitable time, in an amount of 1 to 400 wt parts per 100 wt parts of hydrofluoric acid to a solution containing the chitin-based material and/or the chitosan-based material, hydrofluoric acid and hydrofluoric acid to remove undissolved components from the solution and a step of removing the fluorine component form the solution subjected to the foregoing step.

Claim 15 (currently amended): The process according to ~~any one of claims 8 to 14~~ claim 8 which includes a step of making basic the solution containing the chitin-based material and/or the chitosan-based material, hydrofluoric acid or hydrohalogenated acid other than hydrofluoric acid and hydrofluoric acid at a suitable time to remove undissolved components from the solution after which the solution subjected to the foregoing step is made neutral or acidic.

Claim 16 (currently amended): The process according to ~~any one of claims 8 to 15~~ claim 8, wherein in a step after removing the fluorine component from the solution containing the chitin-based material and/or the chitosan-based material, hydrofluoric acid and hydrofluoric acid, the solution containing the chitin oligomer and/or the chitosan oligomer is brought into contact with at least one species selected from activated carbon, alumina, silica gel, alkyl-containing silica gel, amino-containing silica gel, hydroxyl-containing silica gel, and cyano-containing silica gel.

Claim 17 (currently amended): The process according to ~~any one of claims 8 to 16~~ claim 8 which includes a step of adding a hydrophilic organic solvent in am amount of 1 to 400 wt parts per

100 wt parts of hydrofluoric acid to the solution containing the chitin-based material and/or the chitosan-based material, hydrofluoric acid and hydrofluoric acid to remove undissolved components from the solution and wherein after removing the fluorine component from the hydrophilic organic solvent-containing solution subjected to the foregoing step, the hydrophilic organic solvent-containing solution is brought into contact with at least one species selected from activated carbon, alumina, silica gel, alkyl-containing silica gel, amino-containing silica gel, hydroxyl-containing silica gel, and cyano-containing silica gel.

Claim 18 (currently amended): The process according to ~~any one of claims 8 to 17~~ claim 8, wherein 0.0001 to 1 wt% of a surfactant is added to the solution containing the chitin-based material and/or the chitosan-based material, hydrofluoric acid and hydrofluoric acid at an initial stage of contact between the chitin-based material and/or the chitosan-based material and hydrofluoric acid or hydrogenhalogenated acid other than hydrofluoric acid and hydrofluoric acid.

Claim 19 (original): A process for preparing a chitin oligomer composition and/or a chitosan oligomer composition, the process being characterized by adding hydrohalogenated acid (other than hydrofluoric acid) to a chitin oligomer and/or a chitosan oligomer which is one of the chitin-based material and/or the chitosan-based material.

Claim 20 (original): The process according to claim 19, wherein the chitin oligomer and/or the chitosan oligomer contains at least 70 wt % of oligomer with a polymerization degree of 2 to 40.

Claim 21 (currently amended): The process according to ~~any one of claims 19 and 20~~ claim 19, wherein the concentration of hydrohalogenated acid (other than hydrofluoric acid) is 1 to 70 wt%.

Claim 22 (currently amended): The process according to ~~any one of claims 19 and 21~~ claim 19, wherein the liquid temperature in adding hydrofluoric acid or hydrohalogenated acid (other than hydrofluoric acid) to the chitin-based material and/or the chitosan-based material is adjusted to 25 to 150°C.

Claim 23 (currently amended): The process according to ~~any one of claims 19 and 22~~ claim 19, wherein a basic calcium salt is added to the solution containing the chitin-based material and/or the chitosan-based material, and hydrohalogenated acid other than hydrofluoric acid at a suitable time.

Claim 24 (currently amended): The process according to ~~any one of claims 19 to 23~~ claim 19, which includes a step of adding a hydrophilic organic solvent, at a suitable time, in an amount of 1 to 400 wt parts per 100 st parts of hydrofluoric acid to the solution containing the chitin-based material and/or the chitosan-based material and hydrohalogenated acid (other than hydrofluoric acid) and a step of removing the fluorine component from the solution subjected to the ~~foregoing~~ foregoing step.

Claim 25 (currently amended): The process according to ~~any one of claims 19 to 24~~ claim 19 which included a step of making basic the solution containing the chitin-based material and/or the chitosan-based material, and hydrohalogenated acid other than hydrofluoric acid at a suitable time to remove undissolved components from the solution after which the solution subjected to the foregoing step is made neutral or acidic.

Claim 26 (currently amended): The process according to ~~any one of claims 19 to 25~~ claim 19, wherein a step after removing the fluorine component from the solution containing the

chitin-based material and/or the chitosan-based material and hydrohalogenated acid, the solution containing the chitin oligomer and/or the chitosan oligomer is brought into contact with at least one species selected from activated carbon, alumina, silica gel, hydroxy-containing silica gel, and cyano-containing silica gel.

Claim 27 (currently amended): The process according to ~~any one of claims 19 to 26~~ claim 19 which includes a step of adding a hydrophilic organic solvent in an amount of 1 to 400 wt parts per 100 wt of hydrofluoric acid to the solution containing the chitin-based material and/or the chitosan-based material and hydrohalogenated acid to remove undissolved components from the solution and wherein after removing the fluorine component from the solution containing the hydrophilic organic solvent subjected to the foregoing step, the hydrophilic organic solvent-containing solution is brought into contact with at least one species selected from activated carbon, alumina, silica gel, alkyl-containing silica gel, amino-containing silica gel, hydroxyl-containing silica gel, and cyano-containing silica gel.

Claim 28 (currently amended): The process according to ~~any one of claims 19 to 27~~ claim 19, wherein 0.0001 to 1 wt% of a surfactant is added to the solution containing the chitin-based material and/or the chitosan-based material and hydrohalogenated acid other than hydrofluoric acid at an initial stage of contact between the chitin-based material and/or chitosan-based material and hydrofluoric acid.

Claim 29 (currently amended): A feed for marine animals mainly composted of the chitin oligomer composition and/or the chitsan oligomer composition as defined in ~~any one of claims 1 to 6~~ claim 1.